

Compound Semiconductors Overview and Comparative Study

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Abstract—

The rapid development in the field of electronics and communication are pushing semiconductor materials beyond the conventional limits set by silicon. This review shows the specific characteristics, advantages, and limitations of compound materials like Silicon Carbide, Gallium Nitride and Gallium Arsenide. Concerning applications in the field of high power and high frequency applications, and those concerning extreme environments. It outlines the nature of these materials that has to be investigated from both the physical and electrical viewpoints so that adequate development of devices can be performed in certain areas to outperform silicon's performance in power electronic and System on Chip applications. Results will be interpreted in view of the strategic position held by compound semiconductors and will point the way to future generations of high performance electronics.

I. INTRODUCTION

The rapid advances in modern electronics and communication technologies are driving an increasing demand for semiconductor materials that can operate efficiently under conditions of high power, high frequency, and high temperatures. Silicon (Si) has formed the backbone of the semiconductor industry due to its abundant availability. Semiconductors are the heart of most modern devices and are integral components. The silicon-based semiconductor has, in particular, revolutionized many industries by enabling large-scale production of reliable and high-performance electronics. From consumer electronics and telecommunications to renewable energies and automotive systems, due to its versatility and cost, silicon has become the material predominantly used in semiconductors. But as the applications push beyond silicon's performance limits, especially in areas like power electronics, radio frequency communications, and operation under extreme conditions, the need for new materials has become very important. Silicon faces significant challenges in meeting the evolving needs of next-generation applications.[1]

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In response to these, researchers are increasingly turning towards alternative materials such as Silicon Carbide (SiC), Gallium Nitride (GaN), and Gallium Arsenide (GaAs). Unlike silicon, these materials have wide bandgaps, high electron mobility, and good thermal conductivity. Compound semiconductors are those composed of two or more elements, generally from different groups in the periodic table. The unique properties of compound semiconductors result from its atomic arrangement and bonding features, which make them far more capable of withstanding high energy levels and environmental stresses than silicon. With the growing demand for more efficient and longer-lasting electronic devices, compound semiconductors increasingly become recognized as enabling materials for the next-generation products.

This paper provides a comprehensive study of Compound Semi Conductors, evaluating of SiC, GaN, and GaAs of their physical and electrical characteristics, their respective advantages in various applications and to enhance the potential of silicon in System on Chip (SoC) applications. By examining the limitations of traditional silicon and exploring the strengths of compound semiconductors this research aims to highlight the role of these materials in the evolution of high performance electronics and assess alternatives in next generation technologies.

II. COMPOUND SEMICONDUCTOR MATERIALS

Compound semiconductors are formed with two or more elements from different groups in the periodic table. These compounds have superior electrical, thermal, and optical properties that make them applicable in special applications where the traditional semiconductors based on silicon would be inappropriate.

A. Silicon Carbide (SiC)

Silicon Carbide (SiC) is a compound semiconductor formed from silicon (Si) and carbon (C) atoms. Celebrated for its exceptional physical and electrical properties that make it invaluable in demanding high power and high temperature applications. Unlike silicon SiC has a wide bandgap of 3.26

eV, allowing it to perform efficiently at higher voltages and temperatures, which is essential in power electronics where maximizing efficiency is critical. One of the standout characteristics of SiC is its high breakdown voltage, enabling it to withstand stronger electric fields than silicon and thereby handle high voltage applications with less energy loss. This contributes directly to the improved efficiency and reliability of SiC based power devices. Additionally, SiC boasts superior thermal conductivity around 3.5 W/cm·K it is more than three times that of silicon, allowing it to handle heat more effectively. This property reduces the need for extensive cooling systems supporting compact device designs in high power systems. Furthermore, SiC's high resistance to radiation damage makes it highly suitable for use in extreme environments such as aerospace, nuclear and military applications, where exposure to radiation and high temperatures is a challenge for conventional semiconductor materials. Together, these properties position SiC as a critical material in the advancement of next generation electronics.[4]

1) Bonding: Silicon Carbide (SiC) has a strong covalent bond formed between silicon (Si) and carbon (C) atoms arranged in a crystal structure that can exist in multiple polytypes. The most common being the hexagonal structure known as 4H-SiC. In SiC each silicon atom shares electrons with four surrounding carbon atoms and creating a network of stable covalent bonds. Both silicon and carbon have similar electronegativities so their bonding is almost purely covalent with minimal ionic character

B. Gallium Nitride (GaN)

Gallium Nitride is a wide bandgap compound semiconductor containing gallium and nitrogen. It is well known to possess excellent electrical and optical properties, hence being a highly potential material in quite a number of different applications. Using the bandgap of 3.4 eV much higher than 1.1 eV for silicon, GaN devices can work at high voltage and temperature and hence are especially suited in high-power applications. GaN's high electron mobility allows for faster switching speeds—critical in the processing of fast signals in both RF amplifiers and microwave devices. On the other hand, their good thermal conductivity allows the dissipation of heat so that reliable performance under heightened temperature conditions can be insured. GaN devices also have higher durability and resistance to radiation and harsh environmental conditions compared to silicon-based devices, and thus are quite fit for demanding applications in aerospace, military, and industrial sectors.[3]

1) Bonding: Gallium Nitride (GaN) forms a strong covalent bond between gallium (Ga) and nitrogen (N) atoms creating a robust crystal structure. This bonding arrangement arises because gallium with three valence electrons and nitrogen with five valence electrons combine in a way that satisfies their electron requirements. Gallium donates three of its electrons to form bonds with nitrogen atoms allowing nitrogen to achieve a stable electron configuration. Although primarily the Ga–N bond has partial ionic character due to the difference in

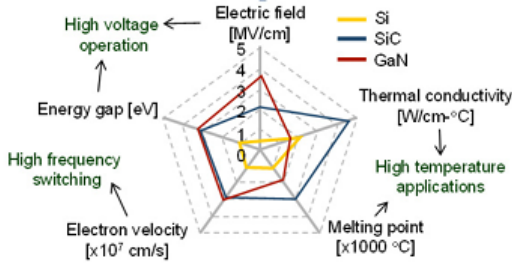
electronegativity between gallium and nitrogen. Nitrogen is more electronegative and causes a slight electron density shift toward nitrogen adding stability to the bond.

C. Gallium Arsenide (GaAs)

Gallium Arsenide is a III–V compound semiconductor, well-known for excellent electronic and optical properties, therefore especially appropriate for high-performance applications in many fields. In contrast to silicon, GaAs presents a direct bandgap energy of 1.42 eV; hence, it may emit and absorb light efficiently—a feature absolutely important for a great number of optoelectronic devices such as light-emitting diodes (LEDs), laser diodes, and photovoltaic cells. GaAs has much higher electron mobility compared to silicon, resulting in faster electron transport and allowing GaAs devices to operate at higher speeds and frequencies. The high electron mobility, along with the high saturation velocity of GaAs, allows for fast signal processing and keeps delay to a minimum, which is ideal for high-frequency applications such as microwave and RF devices in radar and wireless communications. Furthermore, GaAs is reliable at high temperatures for providing better thermal stability than silicon and making it suitable for applications where temperatures fluctuate. In low dimensional semiconductor nanostructures, quantum mechanical effects are directly exploited to customize and dramatically enhance electro-optical properties. Research into the basic electro-optical properties of GaAs-based materials has resulted in several new device concepts, most notably the Quantum Cascade laser. This has, in turn, led to the discovery of new physical phenomena, such as the fractional Quantum Hall effect, and possibly to a whole new class of opto-electronic devices with genuine quantum functionality.[2]

1) Bonding: Gallium Arsenide (GaAs) forms a strong covalent bond between gallium (Ga) and arsenic (As) atoms organized in a zinc blende crystal structure. In GaAs each gallium atom shares electrons with four neighboring arsenic atoms and each arsenic atom does the same with four neighboring gallium atoms creating a stable and orderly structure. The Ga–As bond also has partial ionic character due to the difference in electronegativity between gallium and arsenic, arsenic is more electronegative so it attracts electrons more strongly and creating a slight charge separation in the bond.

Gallium Arsenide (GaAs), Silicon Carbide (SiC), and Gallium Nitride (GaN) are three advanced compound semiconductors each with unique properties that suit specific high performance applications. GaAs with its direct bandgap of 1.42 eV excels in optoelectronics, Silicon Carbide on the other hand has a wide bandgap of 3.26 eV and is known for its remarkable thermal conductivity and high breakdown voltage. GaN, similar to SiC with a wide bandgap of 3.4 eV and also offers high electron mobility and thermal conductivity. Together these materials expand the capabilities of modern electronics beyond the limitations of traditional silicon enabling efficient performance in demanding environments.



Comparison between key material properties[5]

III. USER CASES

A. Silicon Carbide (SiC)

Silicon Carbide (SiC) is an advanced compound semiconductor widely valued in high power high temperature applications that demand high efficiency surpassing traditional silicon in challenging conditions. SiC's superior capabilities make it essential in diverse areas. In electric vehicles (EVs) in their charging infrastructure SiC MOSFETs and diodes enable more efficient power management and faster charging extending EV range and reducing energy loss. Industrial power systems including motor drives and inverters, benefit from SiC's high thermal conductivity and voltage tolerance, enhancing energy efficiency and reducing system size. SiC is also crucial in aerospace and defense where its radiation resistance and extreme temperature resilience support satellite power systems and military radar with enhanced performance and durability. Additionally, renewable energy systems such as solar and wind installations utilize SiC-based inverters to improve power conversion efficiency and enable compact, efficient designs that reduce overall costs. High-voltage power transmission particularly HVDC systems benefits from SiC's capacity to handle high voltages with minimal energy loss over long distances. In medical devices like MRI and X-ray machines SiC's efficient power handling and compact design improve both safety and reliability. For data centers and 5G telecommunications SiC components reduce power consumption and heat generation allowing for efficient cooling and reliable high-speed performance. Overall, SiC's distinctive properties support advancements in energy efficiency, compact device designs and improved resilience across a range of industries where conventional silicon technology falls short.[]

B. Gallium Nitride (GaN)

Gallium Nitride (GaN) is a versatile compound semiconductor that has a broad range of applications, from optoelectronics to power electronics, most especially where high power, high frequency, and efficiency are demanded. In power electronics, GaN transistors and diodes are applied in fast chargers and power supplies for consumer electronics; smaller and lighter adapters with reduced heat generation during charging can

be achieved with these chips. In electric vehicles and their charging infrastructure, GaN improves inverter and onboard charger efficiency, enabling high-speed DC fast charging with a contribution to compact system designs. Its superior characteristics make it also perfect for 5G telecommunications, used to power RF systems and microwave devices critical for rapid data transmission and the best network performance. With all its applications in aerospace and defense, GaN faces extremely high conditions while maintaining durability and performance in applications in satellites and military radar systems. In addition, GaN has been increasingly adopted in renewable energy systems for enhancing efficiency in solar inverters and wind turbines, thanks to its high thermal conductivity that allows it to work effectively at high temperatures. GaN technology has brought the highest fidelity and efficiency in audio amplification and consumer electronics, enabling improved sound quality in audio systems and compact, powerful power adapters. Lastly, in the field of medical devices, GaN helps in the development of reliable imaging equipment, which enables better performance in demanding healthcare environments. All in all, the unique properties of GaN make it an innovation driver across different sectors and one of the best choices where traditional silicon solutions may become insufficient.

1) *Gallium Arsenide (GaAs)*: Gallium Arsenide (GaAs) is a versatile compound semiconductor with applications spanning high speed and high frequency electronics, optoelectronics, and advanced renewable energy systems. Its high electron mobility and direct bandgap make it indispensable in RF and microwave devices used in wireless communications, radar and satellite systems. GaAs is also a key material in LEDs, laser diodes and photodetectors supporting technologies like fiber optics and consumer electronics. In space and defense, its radiation resistance and high efficiency make it a preferred choice for satellite power systems and secure communications. Additionally GaAs solar cells power space probes and concentrated photovoltaic systems while its role in medical devices and quantum research continues to expand. GaAs's unique properties enable it to excel in scenarios where conventional silicon struggles, driving innovation across industries

IV. ADVANTAGES AND DISADVANTAGES

A. Silicon Carbide(SiC)

Silicon Carbide(SiC) has emerged as a highly advantageous material over traditional silicon in high-power applications offering numerous benefits such as higher efficiency, compact size and faster switching speeds. One of the key advantages of SiC is its wide bandgap and high breakdown voltage which allow SiC-based devices to operate at much higher voltages and temperatures than their silicon counterparts. This enables SiC devices to minimize energy losses during power conversion making them more efficient and suitable for applications that demand high power handling, such as electric vehicles, renewable energy systems and industrial power electronics. Additionally SiC's superior thermal conductivity allows for more compact designs by reducing the need for large heat sinks and extensive cooling systems, a major advantage in

automotive and power electronics, where space and weight are critical factors. The ability of SiC to handle faster switching speeds also contributes to its performance benefits, as it enables high-frequency applications with reduced electromagnetic interference (EMI) and enhanced signal integrity. This makes SiC ideal for systems that require precise control and high reliability such as inverters in renewable energy setups and power conversion units in electric vehicles.

However while SiC provides significant advantages, there are challenges that come with its use. The production of SiC is more expensive than silicon, largely due to the complex and costly process of growing high-quality SiC crystals. Furthermore, SiC is much harder than silicon, which makes it difficult to etch, shape, and process, requiring specialized equipment and advanced manufacturing techniques. This results in higher manufacturing costs and complexity limiting its widespread use in the short term. Despite these challenges the future outlook for SiC remains positive. Ongoing advancements in SiC manufacturing processes such as improved crystal growth techniques and better device integration methods, are steadily reducing costs and improving the material's availability. As demand continues to grow for high-efficiency power electronics, particularly in industries like electric vehicles, renewable energy and high-power electronics, the adoption of SiC is expected to increase significantly. With future developments focused on improving material quality and reducing production costs SiC is likely to play a key role in the next generation of power electronics offering unprecedented efficiency, compactness and performance.[6]

B. Gallium Nitride (GaN)

Gallium Nitride (GaN) has emerged as a highly advantageous material in semiconductor applications due to its superior physical and electrical properties compared to traditional silicon. With a wide bandgap of 3.4 eV significantly greater than silicon's 1.1 eV, GaN can operate efficiently at much higher voltages, temperatures, and frequencies. Its ability to support faster switching speeds with minimal energy losses further enhances its appeal in high-speed operations and high-efficiency power supplies. Additionally, GaN's superior thermal conductivity enables effective heat dissipation, reducing the need for extensive cooling systems and facilitating more compact and lightweight designs, especially beneficial in power electronics, EV chargers and telecommunications equipment. High electron mobility in GaN contributes to faster electron transport, lower resistance and higher efficiency which are critical for applications. Moreover, its high breakdown voltage allows GaN devices to sustain higher electric fields making them capable of handling greater voltages and power densities with minimal energy losses.

Despite these key advantages gallium nitride still has many hurdles to overcome before it sees general adoption compared to silicon. The first reason is that the making of gallium nitride devices is much costlier because the processes of growing GaN wafers, generally grown on extremely expensive substrates such as silicon carbide or sapphire, extremely high manu-

facturing costs and problems with scalability. Manufacturing processes for GaN are less mature and compared with silicon, mostly standardized, with limited manufacturing infrastructures, which introduces complexity and raises costs. Also dependence on special materials reduces the availability and scalability of Gallium Nitride compared to widely available silicon. Defects in the crystal structure, because of the lattice mismatch in growing GaN on foreign substrates, for example thermal expansion misfit. While silicon has had the advantage of decades of optimization and widespread adoption, GaN is relatively new and some of the applications have very limited long term reliability data thereby limiting the velocity of its market penetration. Furthermore, the semiconductor ecosystem is still developing, so adoption will also be slower in those industries that most depend on standardized, mature processes.[6]

C. Gallium Arsenide (GaAs)

On the contrary, Gallium Arsenide has a lot of advantages compared to silicon in some semiconductor applications, which make it perfect for high performance and specialty technologies. One of the major advantages of GaAs is its direct bandgap of 1.42 eV, allowing it to effectively emit and absorb light. This makes it highly applicable in optoelectronic devices, such as light emitting diodes, laser diodes and photovoltaic cells, where energy and precision are the most connected issues. It also has higher electron mobility compared to silicon, which actually means electrons move faster and performing well under high speeds and frequencies. Gallium arsenide has some advantages over silicon regarding thermal and radiative effects, and it may find applications in aerospace, military, or extraterrestrial uses that require very long service life and reliability.

Most of the pronounced disadvantages of GaAs against its many advantages have to do with its relation to silicon. It is much more expensive because of the rareness of arsenic and because of the complexity of the growth of crystals of GaAs. This reduces the economic viability for mass market applications. Besides, Gallium Arsenide is mechanically brittle which increases the tendency of wafers to fracture while being handled or processed and therefore reduces the manufacturing throughput. Though performing well at high temperatures, it has lower thermal conductivity compared to silicon, which makes heat dissipation less effective under high power operation. Besides that, the growth and removal of GaAs have environmental and safety concerns due to the toxic nature of arsenic hence, their stringently involved management and disposal add to their costliness and complication. Another challenge with GaAs is its integration into the existing semiconductor manufacturing ecosystem. Silicon dominates the industry with a well established and cost effective infrastructure, while GaAs lacks compatibility with silicon-based processes, making large scale integration and manufacturing more challenging. Besides, these wafers are usually much smaller in size than those of silicon, which limits scalability and increases the cost for large

volume applications. Despite these obstacles, GaAs is the perfect material when its special features become highly required for specific applications, including high frequency electronics and optoelectronic devices. Silicon remains in the leading position in mainstream applications due to its cost, availability, and compatibility with established processes.

While SiC, GaN and GaAs have certain advantages over silicon in particular domains, the replacement of silicon by any of them in will not happen anytime soon. Silicon maintains its dominance because it has superior cost efficiency, scalability and compatibility with mature manufacturing ecosystems. These compound semiconductors are more likely to coexist with silicon complementing it in hybrid designs or specialized areas where their unique properties provide a distinct performance advantage rather than outright replacement. In conclusion, while SiC, GaN, and GaAs bring exciting possibilities replacing silicon entirely requires overcoming significant economic and technological hurdles. Instead, they will serve as complementary technologies in a multi-material semiconductor future.

V. FUTURE TRENDS

Ongoing research and advances in Silicon Carbide technology are driving remarkable improvements in the field of semiconductors. Many efforts have been directed to ensure that efficiency and scalability further improve while sustainability is also achieved. This development toward larger SiC wafer sizes will eventually increase manufacturing productivity by reducing production costs, which would further facilitate more pervasive increases in SiC device deployments for mainstream markets. Recent innovations in SiC growth techniques focus on reducing the number of micropipes and dislocations with a view to higher quality wafers for greater reliability and superior performance of SiC devices. Thermal management is under further study, where improvements are needed to achieve even more effective heat dissipation to allow SiC devices to perform at even higher power density. Besides, the integration of SiC and GaN in hybrid power modules enables taking advantage of the good characteristics of both materials for better performance in specialized applications. The study is also channeled to the next generation of SiC devices that would be more appropriate for certain industry needs, including ultra-high voltage applications. Recycling techniques and sustainable practices in SiC production are under development mainly to fall in line with the global goals on sustainability for a greener future in semiconductor technology.[7]

GaN technology has developed to an extent in contributing to making the semiconductor industry more scalable, efficient, and ecologically sound in production. Fabrication of larger GaN wafers will reduce fabrication cost and improve the scalability of production by increased yield of devices and making fabrication more economic. The growth technology has been developed, focusing on high quality and defect free GaN layer. The extension of the application space in the high voltage, high

power density areas is developing vertically GaN-structured-based development and hence places the GaN as a core component in next generation power electronics. In consumer electronics, the use of GaN based chargers and adapters will continue their reduction in size, increase efficiency and lower cost toward a revolution in portable power applications. Advanced packaging methods which could remove heat will have to be developed to assure that the high power density GaN devices do not experience an error. The research into combining GaN with diamond substrates, taking advantage of the high thermal conductivity of diamond, seems to be a promising toward solving the heating problems. Preparation and recycling of GaN in an eco-friendly way have also been developed not to leave an ecological footprint of this promising technology.[7]

Upcoming GaAs technology will be more robust, reliable, and even greener, finding broader applications in the semiconductor field. The development of superior crystal growth techniques is expected to enable the growth of the GaAs crystal with high crystalline quality, low dislocation density and optimized device performance. The reduced presence of impurities and structural defects in the substrates due to these improvements will result in greater reliability, especially when the operation requires high accuracy and durability. Research for environmental concerns involves recycling GaAs materials from end of life devices to reduce waste and production cost. Green manufacturing is a new initiative toward developing such processes that minimize the usage of resources and generation of waste. For applications in special areas such as space and nuclear fields, advances in radiation hardened GaAs devices will result in increased resistance to radiation and long term stability, becoming irreplaceable under extreme environmental conditions. These innovations show the capability of GaAs to fulfill the ever growing demands of modern electronics while keeping up with global sustainability goals.[7]

VI. CONCLUSION

Within new semiconductor technology, a number of compound semiconductors materials are employed, such as Silicon Carbide, Gallium Nitride, and Gallium Arsenide. Each of these has advantages over regular silicon in performance for particular uses. Having superior heat, electricity, and light properties than silicon, their applications go to high performance in power electronics, telecommunications, and even in aerospace systems. They have a limitation to their use due to the high production cost, lack of material availability and difficulty integrating with the current silicon platforms. They won't just outplay silicon but work with it in hybrid systems that will be efficient, compact and reliable in next generations of systems. The key focus areas of research are cost reduction and eco friendliness to harness the true potential of semiconductors

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